

Resource Summary Report

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Oxford: Instruments P 80 Plasma Etcher

RRID:SCR_020364

Type: Tool

Proper Citation

Oxford: Instruments P 80 Plasma Etcher (RRID:SCR_020364)

Resource Information

URL: <https://plasma.oxinst.com/products/pecvd/plasmapro-800-pecvd#product-information-tabs>

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Description: PlasmaPro 800 offers a flexible solution for Plasma Enhanced Chemical Vapour Deposition (PECVD) processes on large wafer batches and 300mm wafers, in a compact footprint, open-loading system. The large wafer platen allows for production scale batch processing and 300mm wafer handling.

Resource Type: instrument resource

Keywords: Oxford, Plasma Etcher, Instrument Equipment, USEDit

Availability: Commercially available

Resource Name: Oxford: Instruments P 80 Plasma Etcher

Resource ID: SCR_020364

Alternate IDs: Model_Number_P80

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260912T195934+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: Instruments P 80 Plasma Etcher.

No alerts have been found for Oxford: Instruments P 80 Plasma Etcher.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.